

Manufacturer/exporters	Margin (percent)
TAMSA	21.70
All Others	21.70

This notice also serves as the only reminder to parties subject to administrative protective orders ("APO") of their responsibility concerning the return or destruction of proprietary information disclosed under APO in accordance with 19 CFR 351.305. Timely notification of the return or destruction of APO materials or conversion to judicial protective order is hereby requested. Failure to comply with the regulations and terms of an APO is a violation which is subject to sanction. This five-year ("sunset") review and notice are in accordance with sections 751(c), 752, and 777(i)(1) of the Act.

Dated: February 28, 2001.

Timothy J. Hauser,

Acting Under Secretary for International Trade.

[FR Doc. 01-5917 Filed 3-8-01; 8:45 am]

BILLING CODE 3510-DS-P

DEPARTMENT OF COMMERCE

National Institute of Standards and Technology

Government Owned Inventions Available for Licensing

AGENCY: National Institute of Standards and Technology, Commerce.

ACTION: Notice of Government owned inventions available for licensing.

SUMMARY: The inventions listed below are owned in whole or in part by the U.S. Government, as represented by the Department of Commerce, and are available for licensing in accordance with 35 U.S.C. 207 and 37 CFR Part 404 to achieve expeditious commercialization of result of federally funded research and development.

FOR FURTHER INFORMATION CONTACT: Technical and licensing information on these inventions may be obtained by writing to: National Institute of Standards and Technology, Office of Technology Partnerships, Building 820, Room 213, Gaithersburg, MD 20899; Fax 301-869-2751. Any request for information should include the NIST docket No. and Title for the relevant invention as indicated below.

SUPPLEMENTARY INFORMATION: The invention listed below was made jointly by scientists from NIST and from Schott Glass Technologies Inc. under the auspices of a Cooperative Research and

Development agreement (CRADA). In 1995 all rights in the invention were assigned to the United States, as represented by the Secretary of Commerce. Pursuant to the terms of the CRADA, Schott Glass currently retains the rights to negotiate, on Schott Glass's behalf, the terms of a non-exclusive commercialization license to the invention. NIST may enter into a CRADA with the licensee to perform further research on the invention for purposes of commercialization. The invention available for licensing is:

NIST Docket Number: 93-039CIP

Title: Integrated Optic Laser

Abstract: A laser waveguide medium

is provided comprising:

A laser glass substrate wherein the substrate is a glass comprising (on an oxide composition basis):

	Mole%
P ₂ O ₅	50-70
Al ₂ O ₃	4-13
Na ₂ O	10-35
La ₂ O ₃	0-6
Ln ₂ O ₃	>0-6
R ¹ O	0-20
R ₂ O	0-18

Wherein Ln₂O₃ is the sum of the oxides, of active lasing lanthanides of atomic number 58-71, R¹O is the sum of oxides of Mg, Ca, Cr, Ba, Zn and Pb, and R₂O is the sum of oxides of Li, K, Rb and Cs; and

A waveguide region embedded in the substrate, the waveguide region having a higher refractive index than the substrate and the waveguide region having an inlet region through which light can enter and an outlet region through which light can exit.

Dated: March 5, 2001.

Karen H. Brown,

Acting Director.

[FR Doc. 01-5848 Filed 3-8-01; 8:45 am]

BILLING CODE 3510-13-M

DEPARTMENT OF COMMERCE

National Institute of Standards and Technology

Announcement of a Meeting To Discuss an Opportunity To Join a Cooperative Research and Development Consortium on High Resolution Diffraction and Reflectometry Standards

AGENCY: National Institute of Standards and Technology, Commerce.

ACTION: Notice of Public Meeting.

SUMMARY: The National Institute of Standards and Technology (NIST)

invites interested parties to attend a meeting on March 29, 2001 to discuss the possibility of setting up a cooperative research consortium. The objectives of this consortium are (1) To define the factors that limit accuracy and precision in high resolution X-ray diffraction and reflectometry analyses of semiconductor materials, and (2) to assist the consortium members in implementing high resolution X-ray diffraction and reflectometry measurements.

DATES: The meeting will take place on March 29, at 10:00 a.m. Interested parties should contact NIST to confirm their interest at the address, telephone number or FAX number shown below.

ADDRESSES: The meeting will take place in NIST North (820), Room 201, National Institute of Standards and Technology, Gaithersburg, MD 20899-8422.

FOR FURTHER INFORMATION CONTACT: Dr. Richard J. Matyi, Physics Building (221), Room A143, National Institute of Standards and Technology, Gaithersburg, MD 20899-0001. Telephone: 301-975-4272; FAX: 301-975-3038; e-mail: richard.matyi@nist.gov.

SUPPLEMENTARY INFORMATION: Any program undertaken will be within the scope and confines of The Federal Technology Transfer Act of 1986 (Public Law 99-502, 15 U.S.C. 3710a), which provides federal laboratories including NIST, with the authority to enter into cooperative research agreements with qualified parties. Under this law, NIST may contribute personnel, equipment, and facilities but no funds to the cooperative research program. This is not a grant program.

The R&D staff of each industrial partner in the consortium will be able to interact with NIST researchers on generic needs for high resolution X-ray diffraction and reflectometry measurements on semiconductor materials. Partners will have an opportunity to work with NIST researchers to identify the factors that limit accuracy and precision in high resolution X-ray diffraction and reflectometry analysis, and to participate in programs to improve the accuracy and precision of these measurements in their own facilities.

Dated: March 5, 2001.

Karen H. Brown,

Acting Director.

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